

ARCNL's Source Department: Physics of Plasma Sources of EUV Light

ARCNL Showcase, November 4th, 2019

Oscar Versolato, ARCNL



Team

ARCNL EUV Plasma Processes group:

Dmitry Kurilovich (ASML scientist)

Francesco Torretti (PhD, now at ASML)

Joris Scheers (PhD) *talk S111*

Subam Rai (PhD, RUG) *talk S108*

Ruben Schupp (PhD)

Jaap Hermens (TU/e MSc)

Job Duffhues (TU/e MSc)

Zoi Bouza (TKI PhD)

Bo Liu (VIDI PhD) *talk S72*

Lars Benhke (VIDI PhD) *poster S77*

Lucas Poirier (ERC PhD) *poster S84*

Javier Hernández (ERC PD)

Laurens van Buuren (technician)

Ronnie Hoekstra (group leader) *talk S81*

Wim Ubachs (group leader)

Oscar Versolato (group leader; dept. head) *this talk S104*

ARCNL EUV G&I group:

Tiago de Faria Pinto (PhD, now STFC)

Randy Meijer (PhD) *talk S109*

Zeudi Mazzotta (PD) *poster S74*

Jan Mathijssen (PhD) *poster S56*

Stefan Witte (group leader) *talk S51*

Kjeld Eikema (group leader)

SOURCE Plasma modeling team

John Sheil (PD) *talk S91*

Diko Hemminga (PhD)

Academic collaborators:

A. Klein (UT, ASML)

S. Reijers (UT)

H. Gelderblom (TU/e) *talk S71*

J.R. Crespo López-Urrutia (MPIK)

H. Bekker (MPIK, now Col. Uni. NY)

A. Ryabtsev (ISAN)

M. Basko (KIAM, ISAN)

A. Borschevsky (Uni. Groningen)

J. Berengut (UNSW Australia)

Muharrem Bayraktar (Uni. Twente) *poster S35*

Fred Bijkerk (Uni. Twente)

James Colgan (LANL) *talk S82*



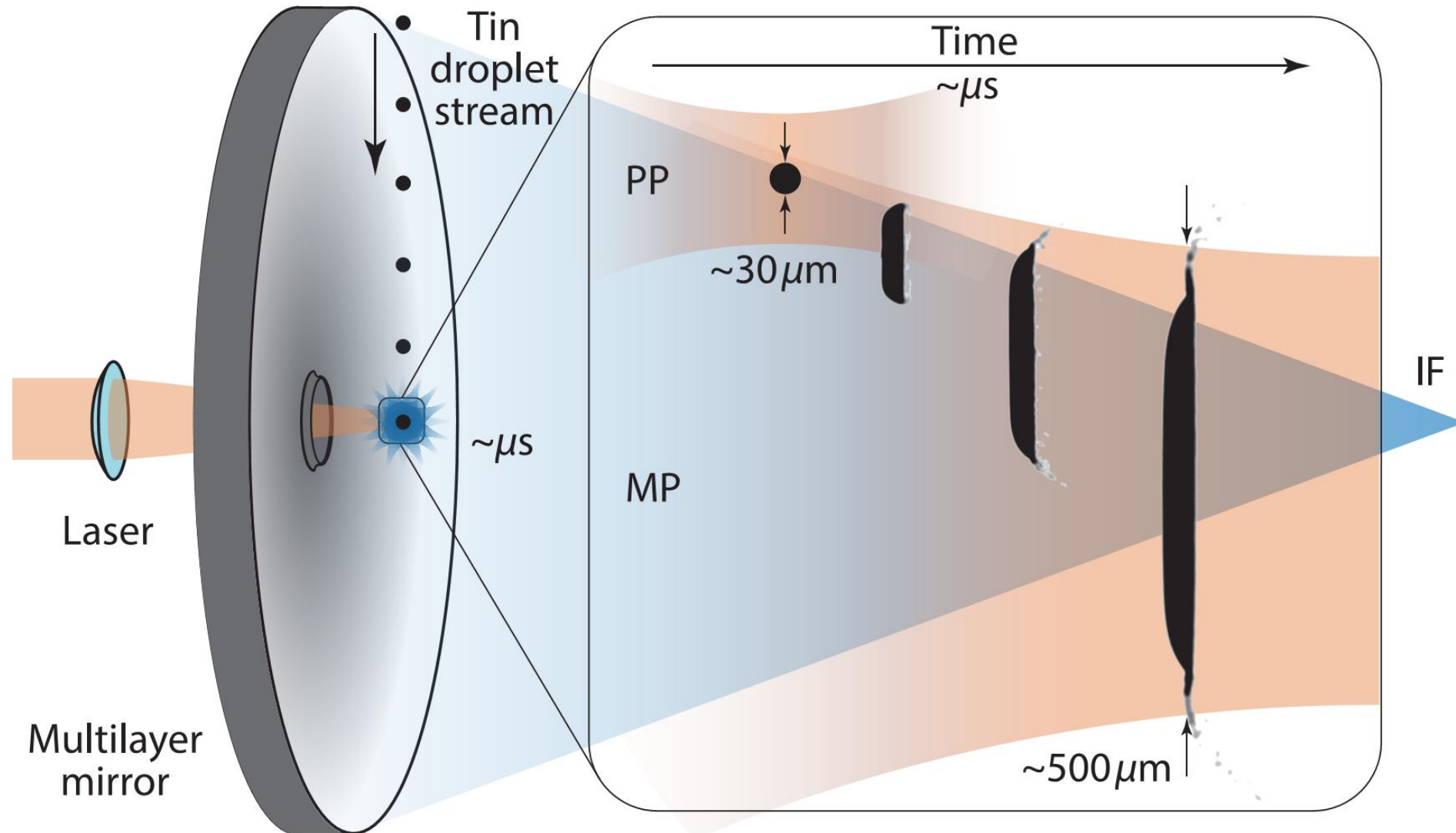
UNIVERSITEIT VAN AMSTERDAM



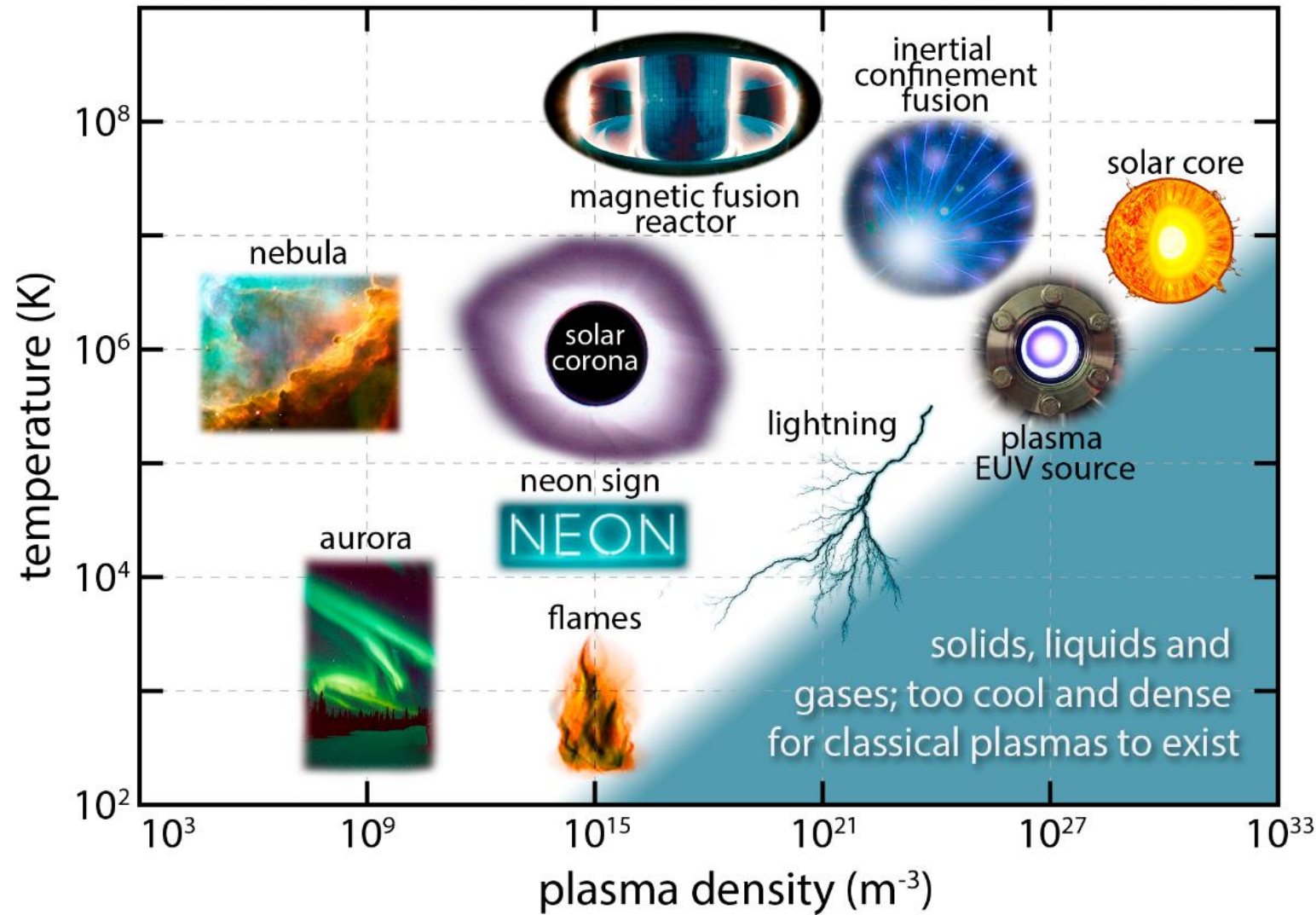
Provincie Noord-Holland



Laser-produced plasma for nanolithography



Position in the plasma universe



RALEF: talk S91

Nd:YAG (ARCNL)

CO₂ (ASML)

$\lambda = 1\mu\text{m}$

$\lambda = 10\mu\text{m}$

$T \sim 30\text{eV}$

$T \sim 25\text{eV}$

$n_e \sim 10^{21}\text{e}/\text{cm}^3$

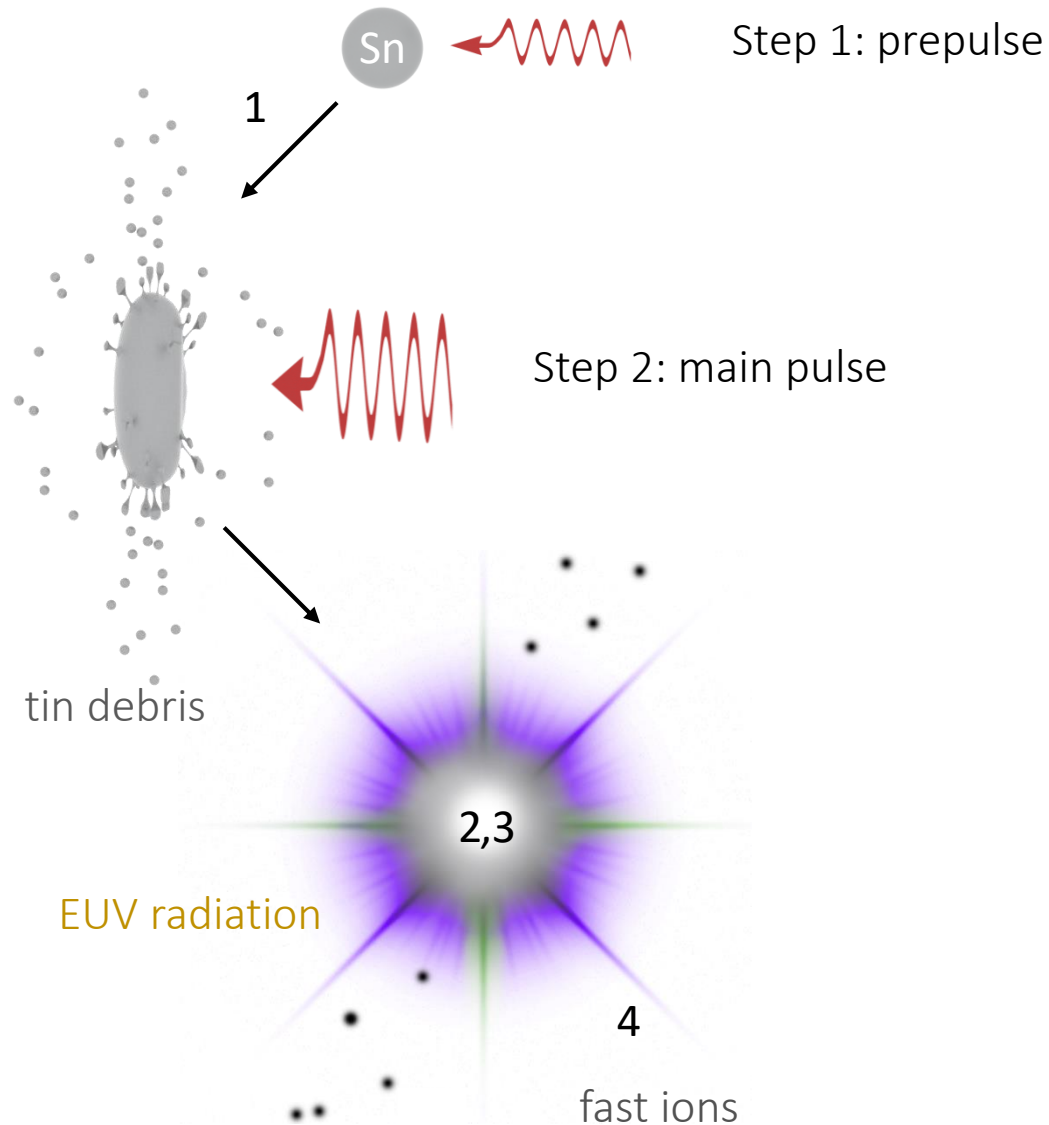
$n_e \sim 10^{19}\text{e}/\text{cm}^3$

$Z \sim 12$

$Z \sim 12$

$n_e \sim \lambda^{-2}$

Physics challenges

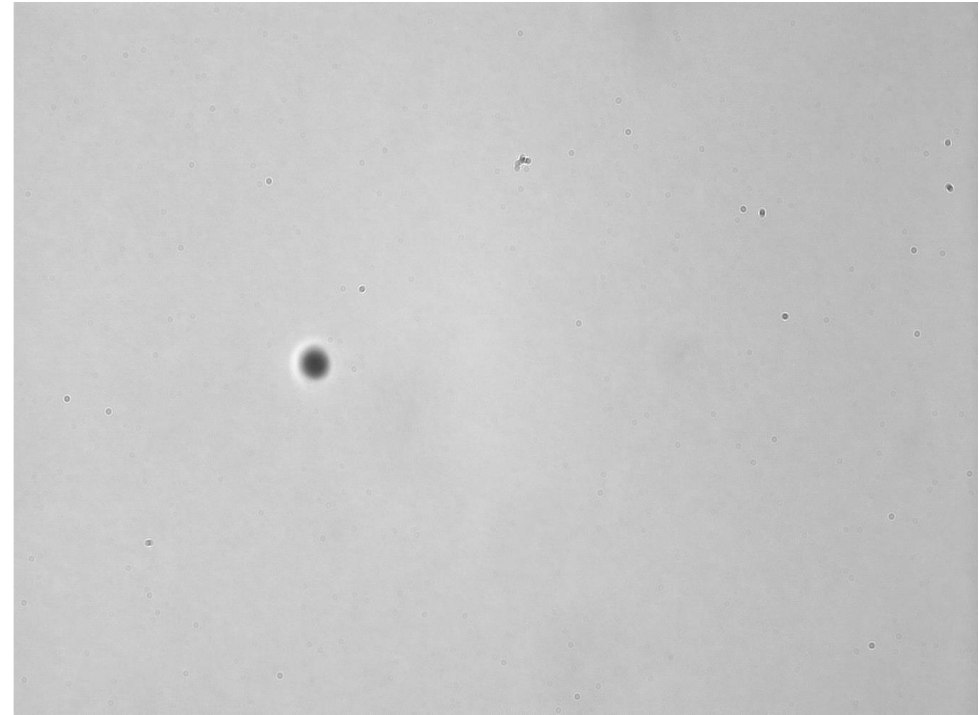
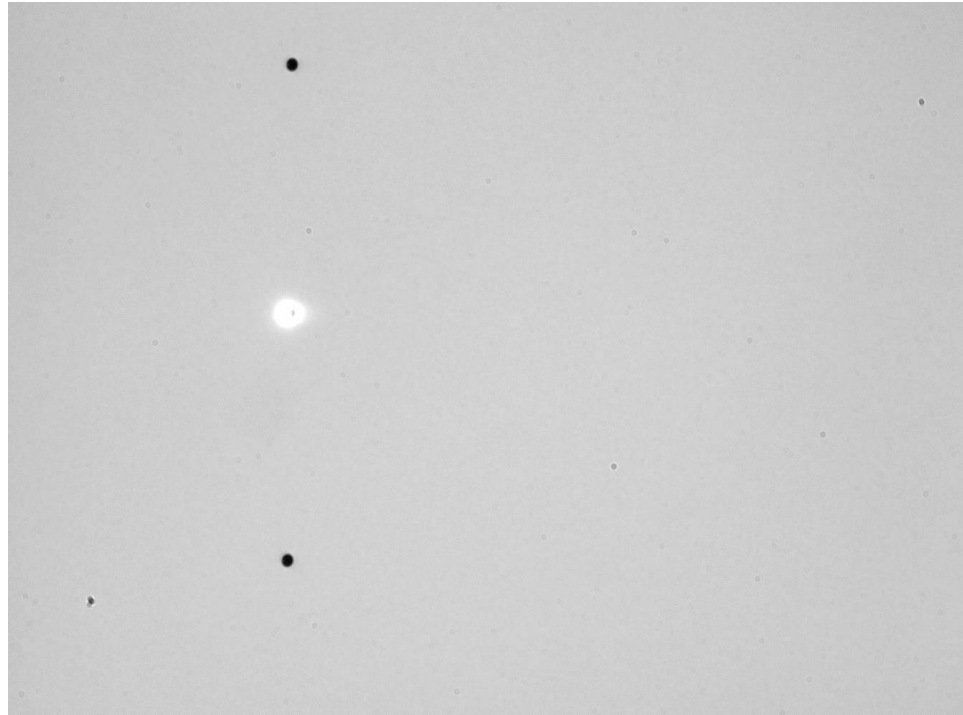
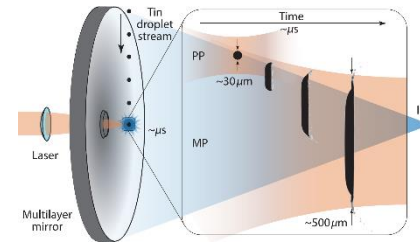


- 1. Understand exploding tin microdroplets**
 - What determines deformation and fragmentation?
- 2. Key insights to enable source predictive modeling**
 - What emits that EUV light?
- 3. Push the fundamental limits of the conversion efficiency**
 - What sets the fundamental limit?
- 4. Control expansion dynamics of laser-produced plasma**
 - What is the cause of the ion energy distribution?

Mass loss from a stretching semi-transparent sheet of liquid tin

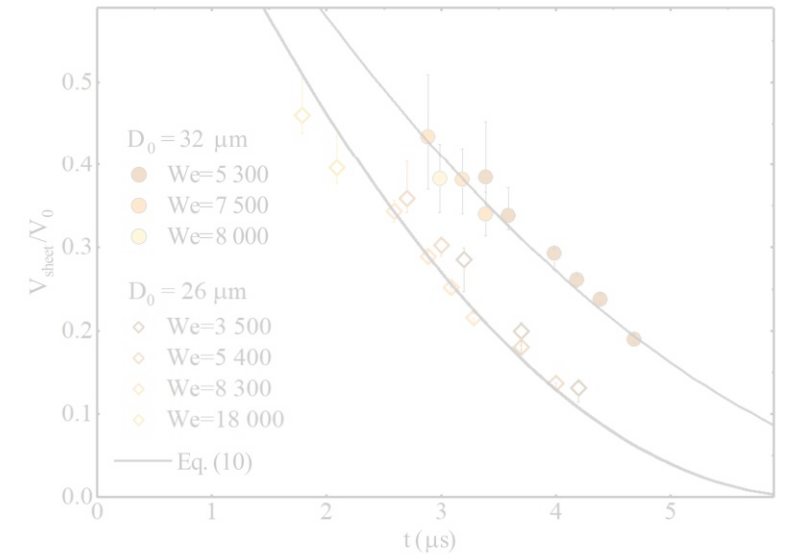
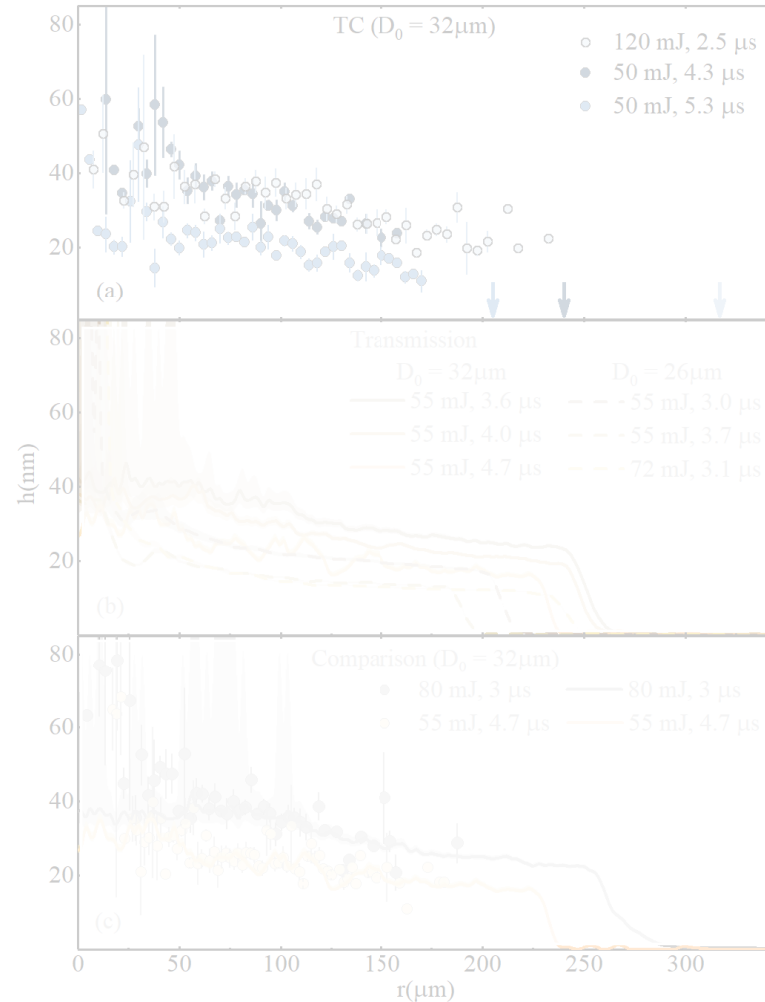
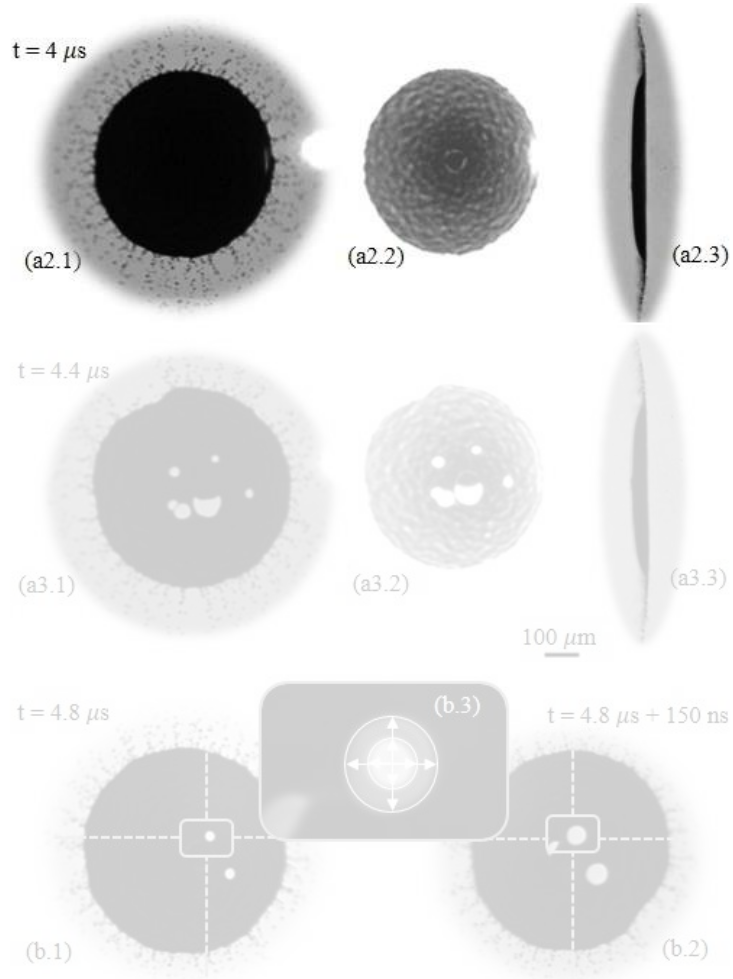
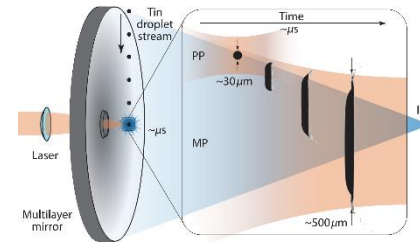
talk S72

talk S71

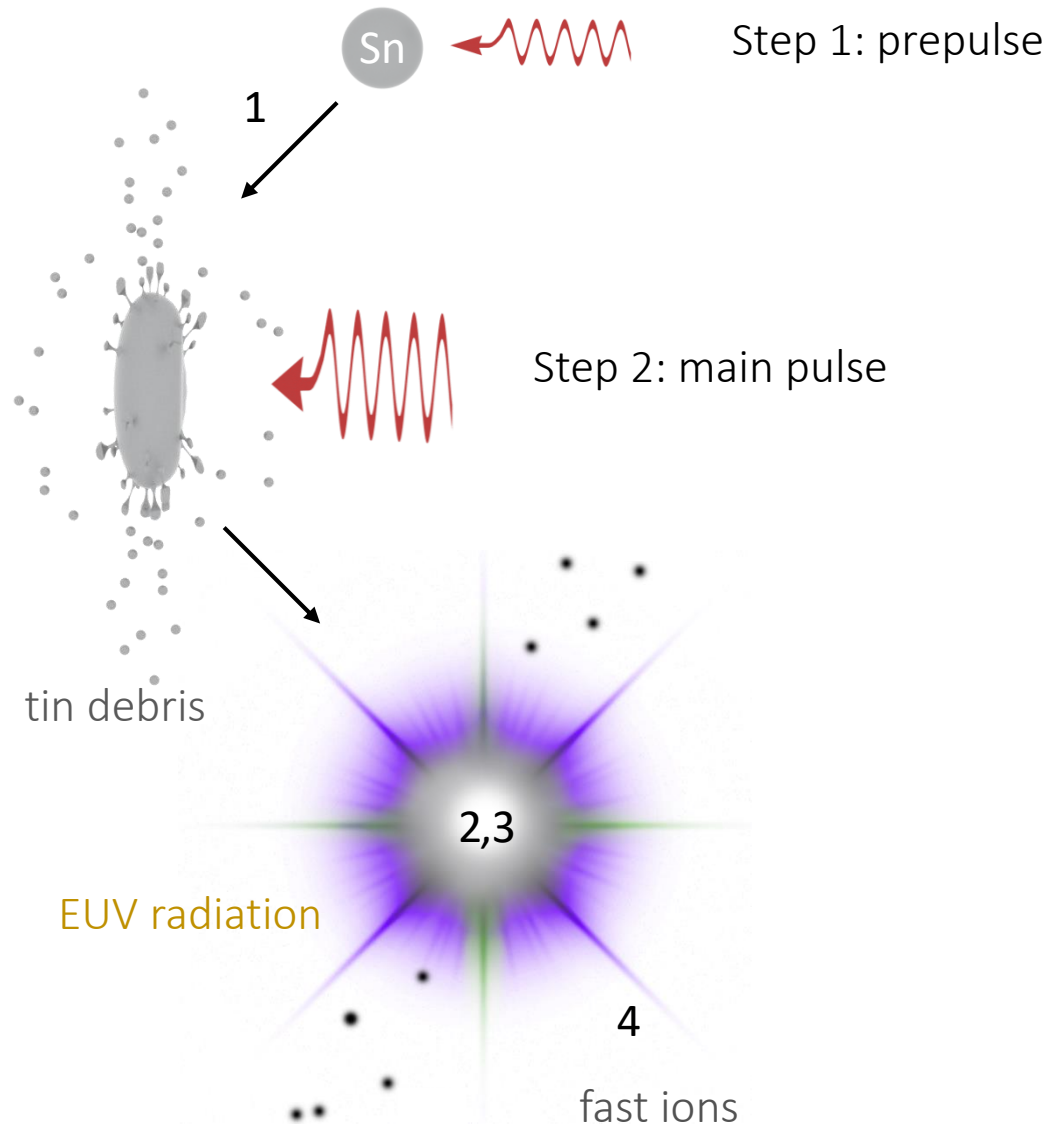


Mass loss from a stretching semi-transparent sheet of liquid tin

talk S72

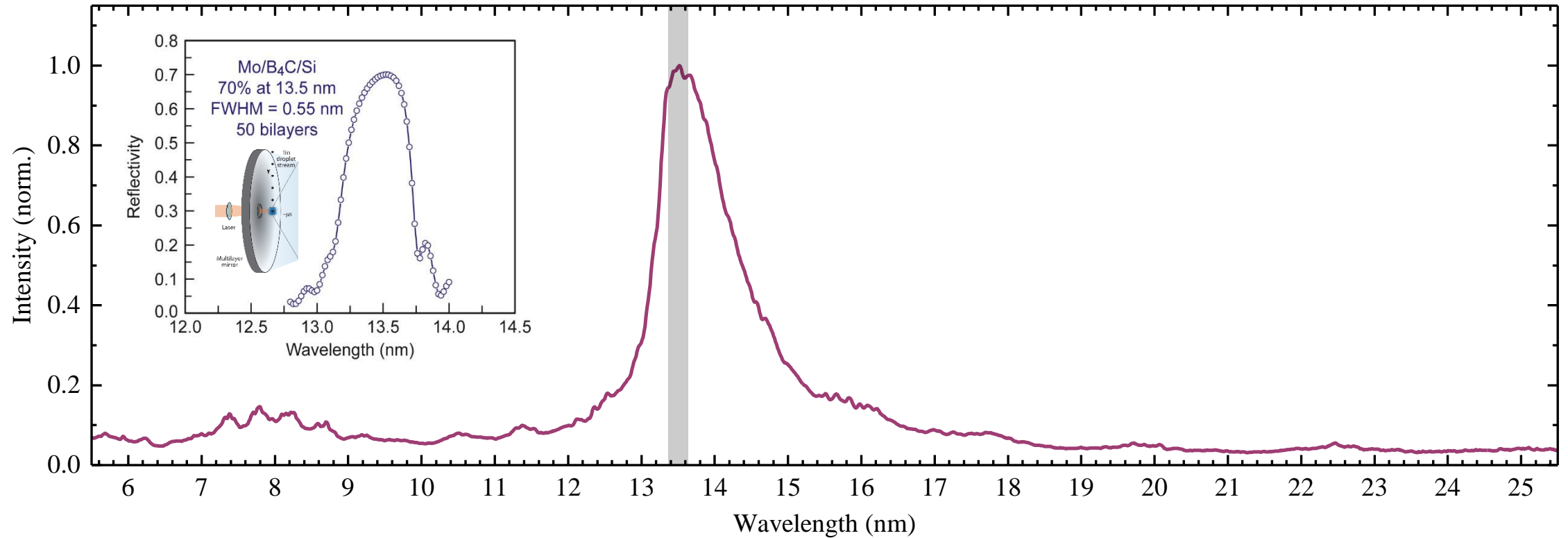


Physics challenges

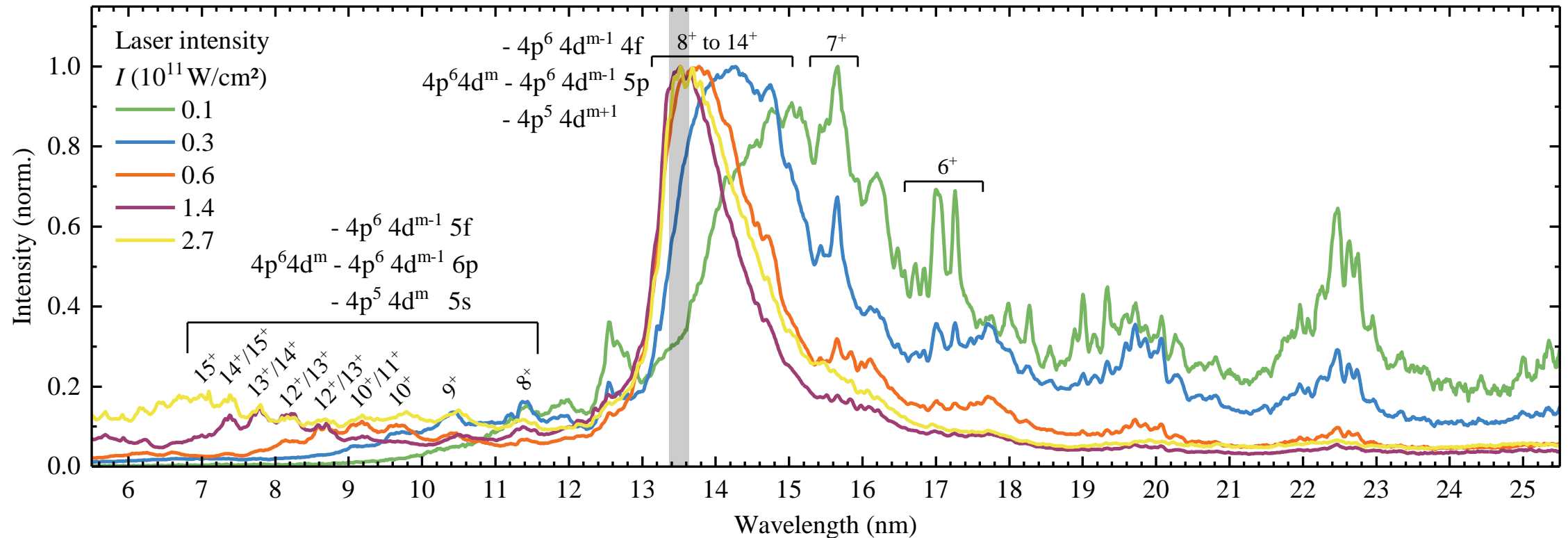


1. Understand exploding tin microdroplets
 - What determines deformation and fragmentation?
2. **Key insights to enable source predictive modeling**
 - What emits that EUV light?
3. Push the fundamental limits of the conversion efficiency
 - What sets the fundamental limit?
4. Control expansion dynamics of laser-produced plasma
 - What is the cause of the ion energy distribution?

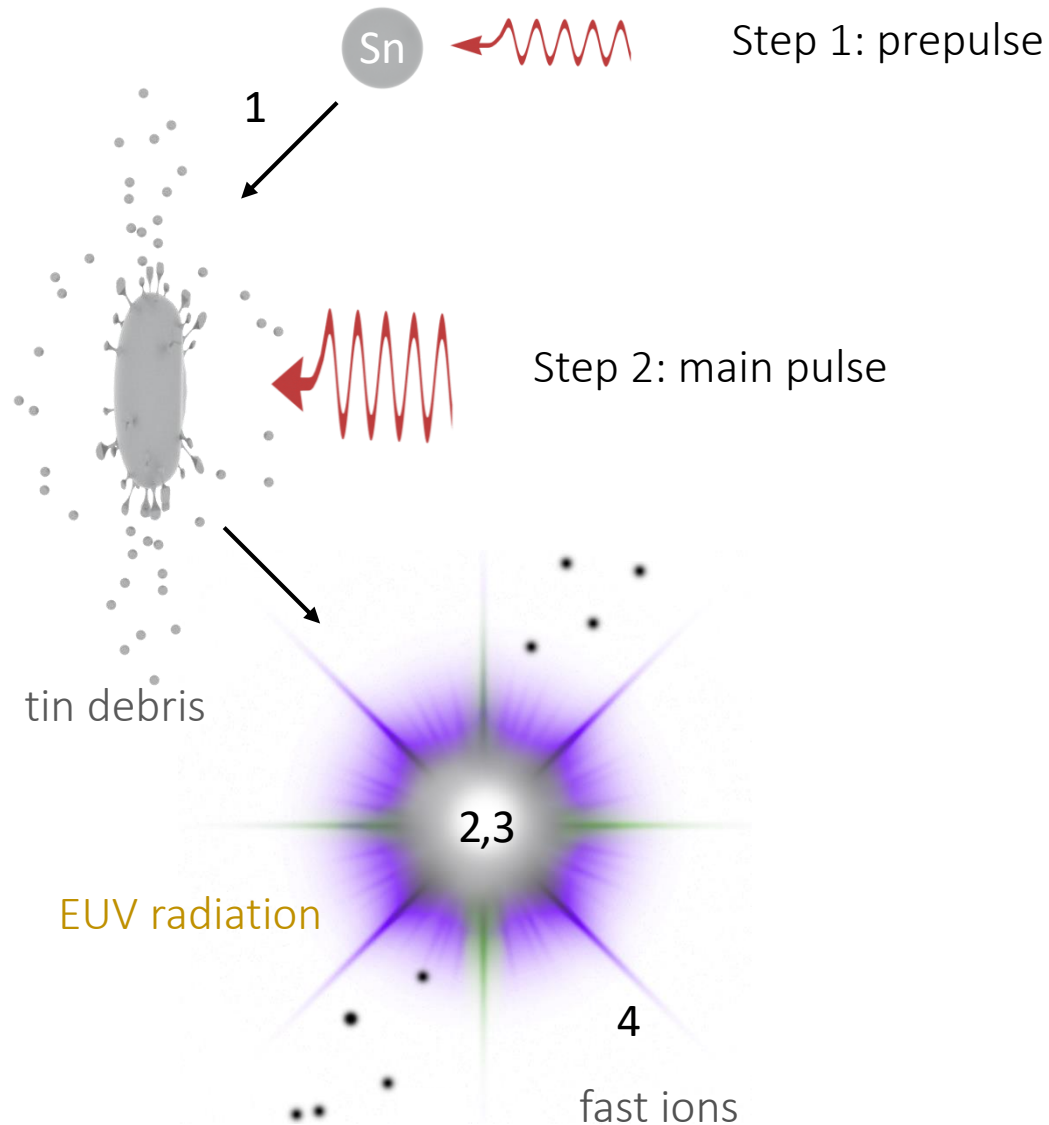
Spectrum of YAG-laser-driven tin plasma



Spectrum of YAG-laser-driven tin plasma: line emission from highly charged tin ions



Physics challenges

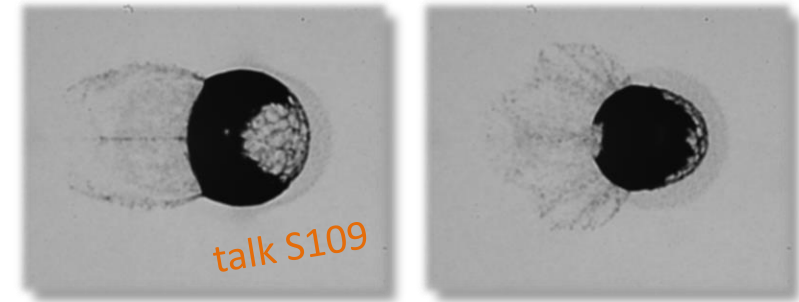


1. Understand exploding tin microdroplets
 - What determines deformation and fragmentation?
2. Key insights to enable source predictive modeling
 - What emits that EUV light?
3. Push the fundamental limits of the conversion efficiency
 - What sets the fundamental limit?
4. Control expansion dynamics of laser-produced plasma
 - What is the cause of the ion energy distribution?

Laser development and EUV source physics

EUVGI team

poster S74

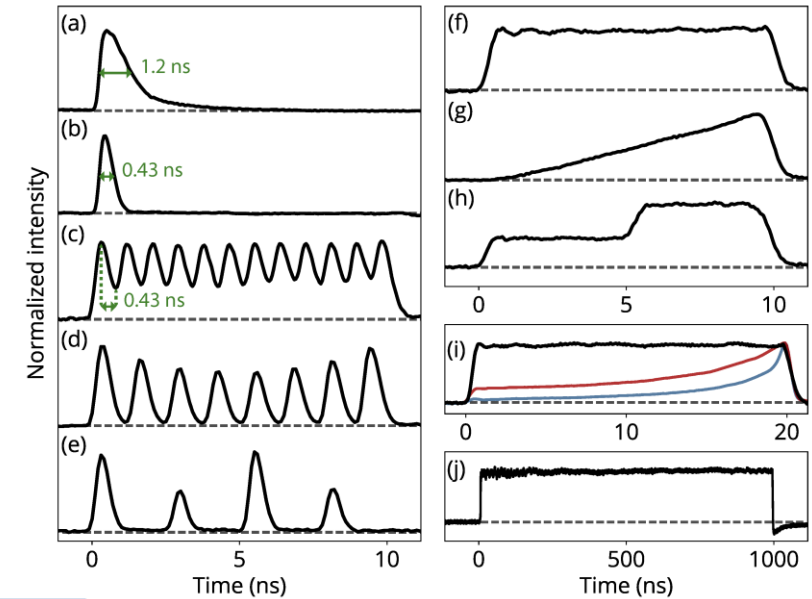


Collaboration with the EUV Plasma Processes group (Oscar Versolato)

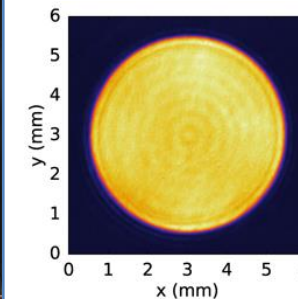
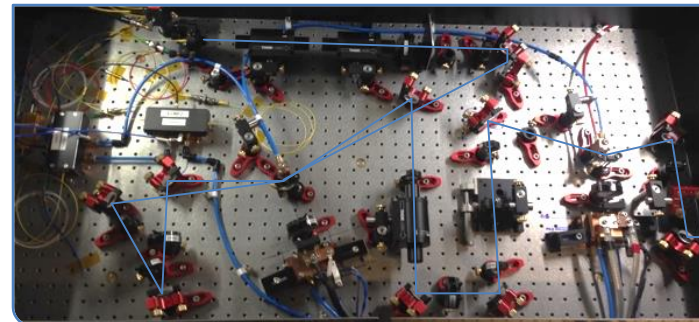
Main objective: Achieving control over LPP target shapes and emission properties through light-field control

Developed laser systems (all single-shot up to 100 Hz):

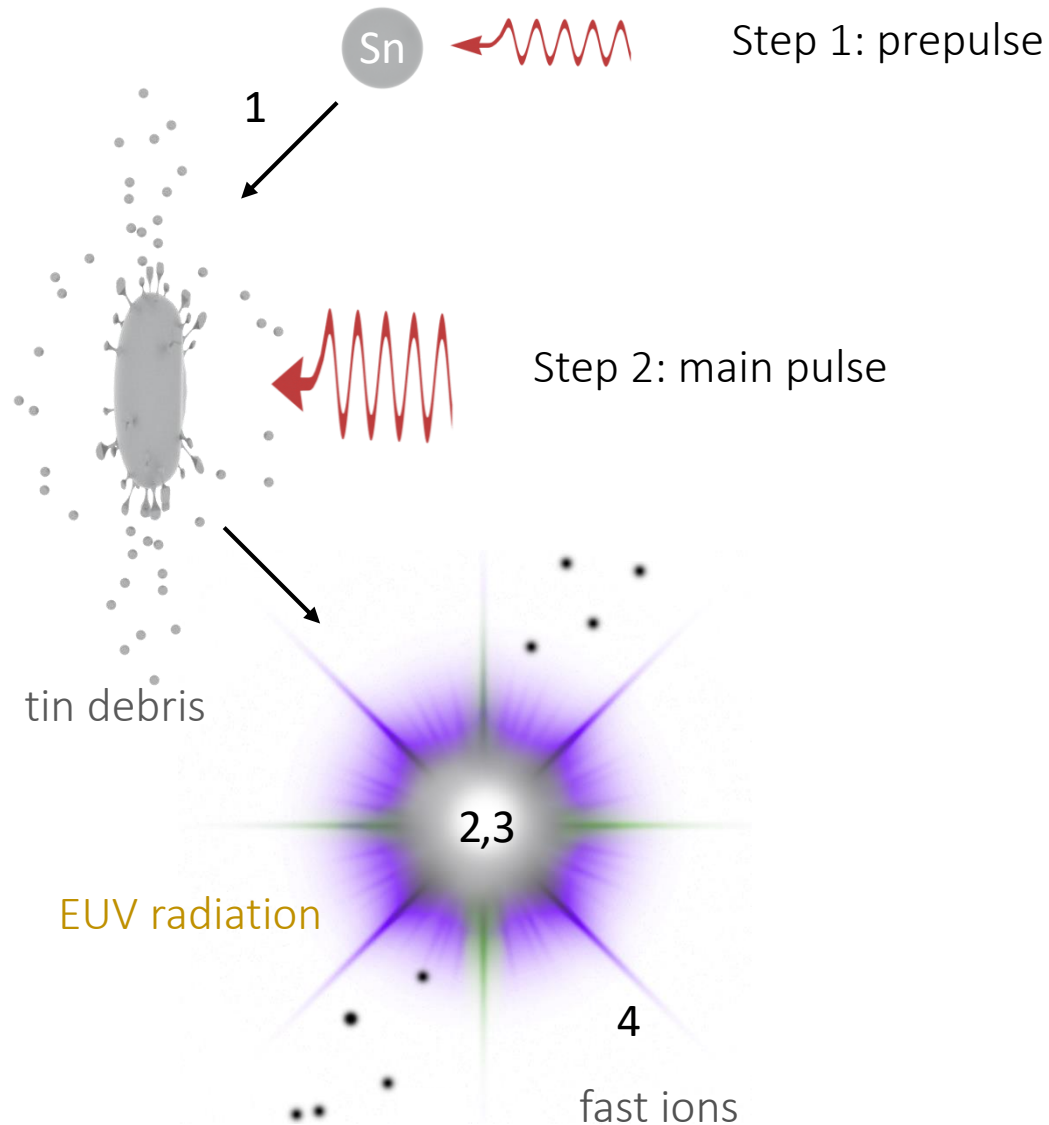
- Nanosecond Nd:YAG system: 0.43 ns to 1 μ s with arbitrary temporal shape, up to 430 mJ, 1064 nm
- Picosecond Nd:YAG amplifier: 15-110 ps, 25-190 mJ, 1064 nm
- Femtosecond parametric amplifier:
 - 1) signal: 200 fs to 30 ps, 10 mJ at 1.55 μ m,
 - 2) idler: 4 mJ at 3.5 μ m, 30 ps (in future also compressible to 200 fs)



Application example: Developing models for influence of pre-pulse parameters on debris generation and target shape (2-5 years).



Physics challenges

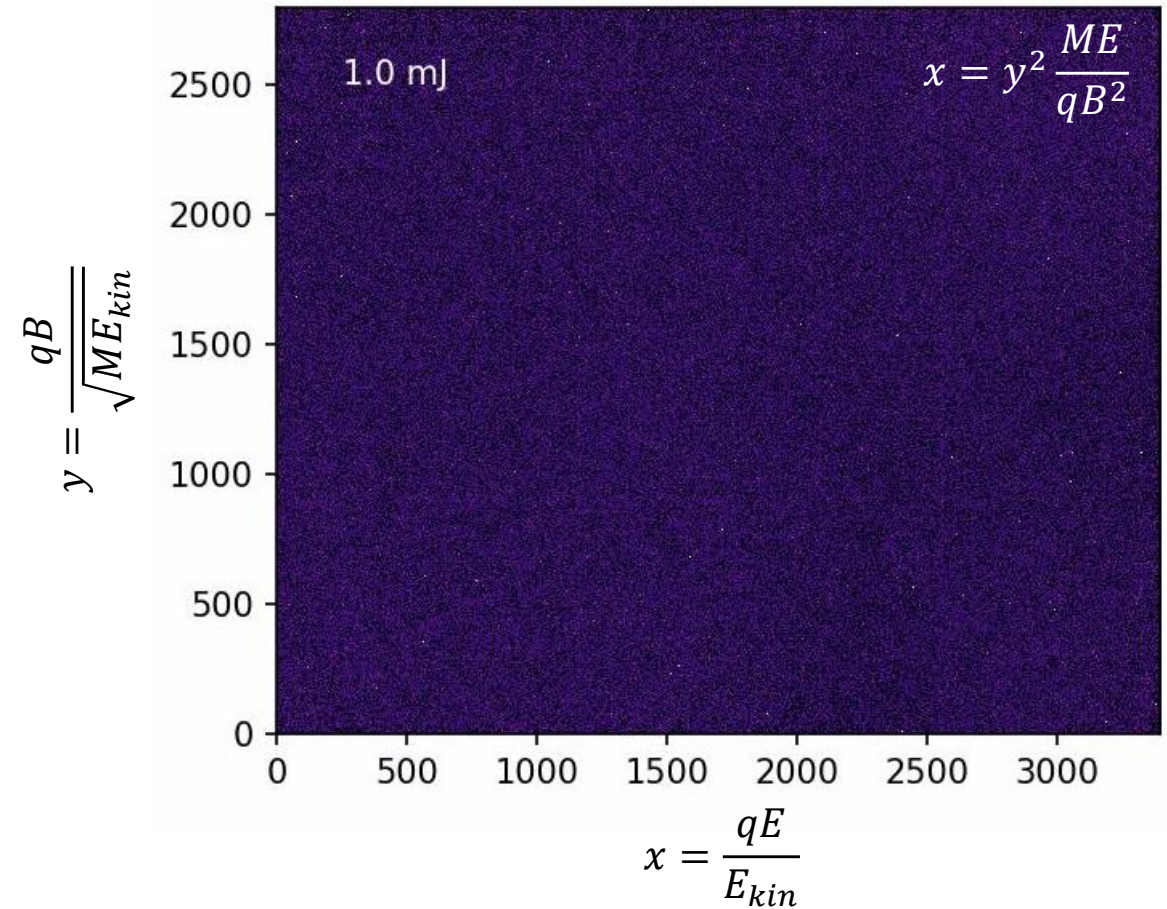
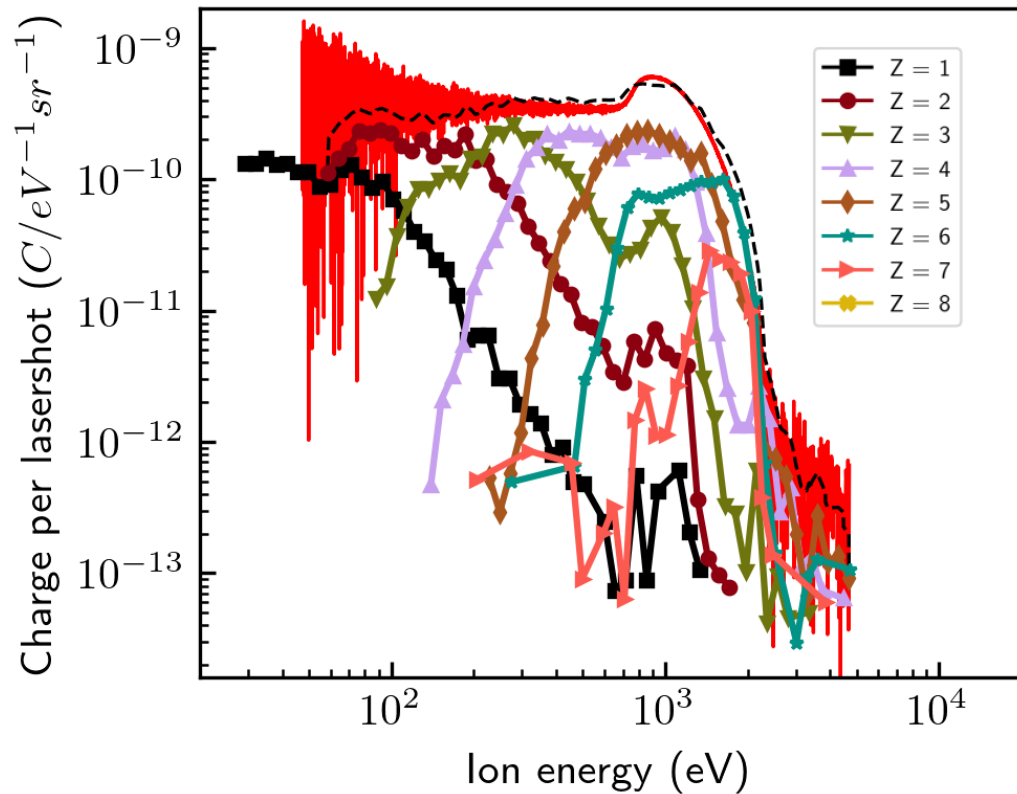


1. Understand exploding tin microdroplets
 - What determines deformation and fragmentation?
2. Key insights to enable source predictive modeling
 - What emits that EUV light?
3. Push the fundamental limits of the conversion efficiency
 - What sets the fundamental limit?
4. **Control expansion dynamics of laser-produced plasma**
 - What is the cause of the ion energy distribution?

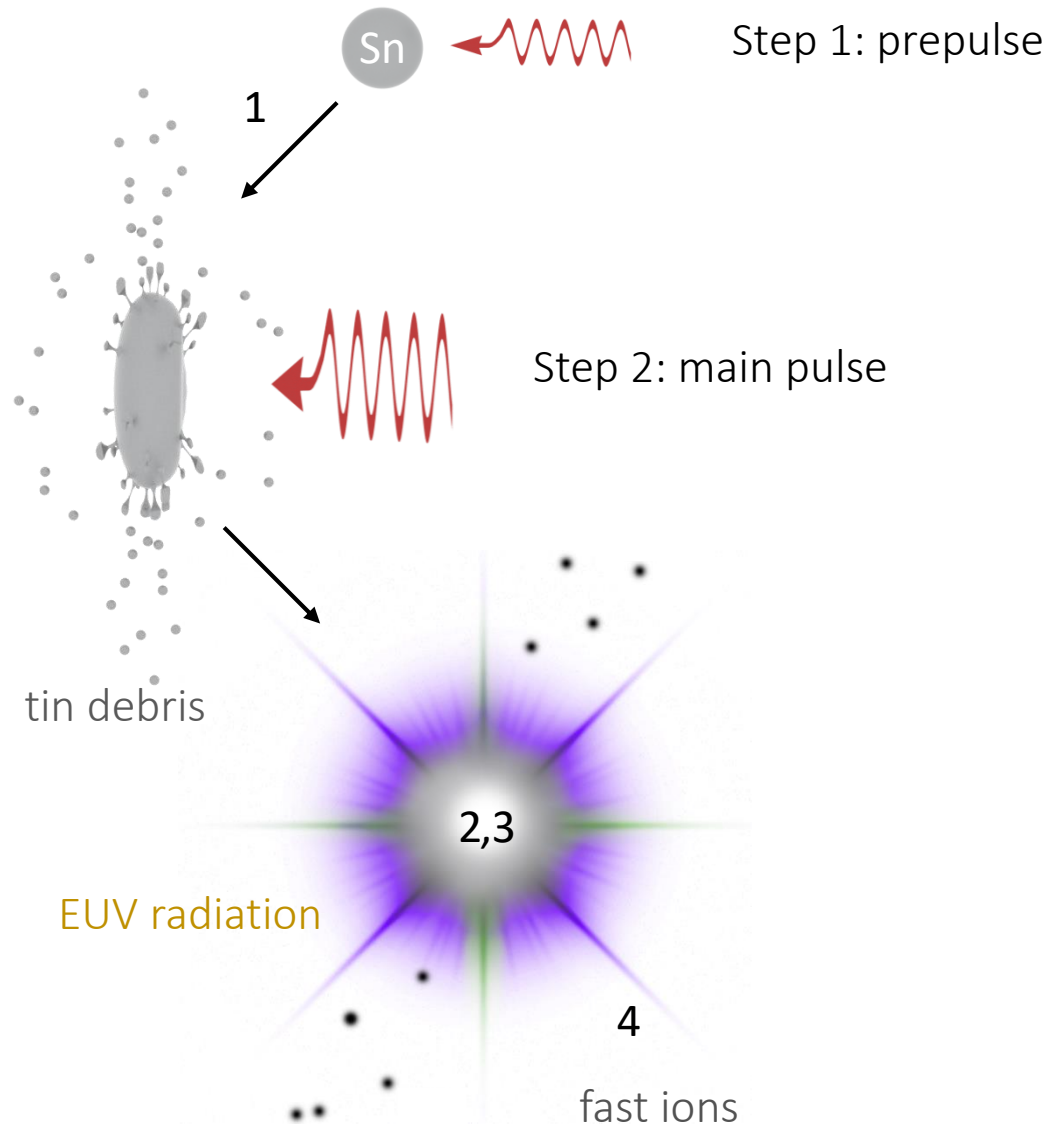
Plasma expansion: tools for charge-state-resolved ion energy spectroscopy

poster S84

talk S108



Physics challenges: outlook



1. **Understand exploding tin microdroplets**
 - What determines deformation and fragmentation?
2. **Key insights to enable source predictive modeling**
 - What emits that EUV light?
3. **Push the fundamental limits of the conversion efficiency**
 - What sets the fundamental limit?
4. **Control expansion dynamics of laser-produced plasma**
 - What is the cause of the ion energy distribution?